

PRESS RELEASE

Lasertec Corporation

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Lasertec Releases New Mask Blank Inspection and Review Systems, the MAGICS Series M9750 and M9751

Yokohama, December 8, 2025 – Lasertec Corporation today announced the release of the MAGICS series M9750 and M9751 (collectively "M9750/51") mask blank¹ inspection and review systems. These new systems deliver a significant enhancement in sensitivity and throughput compared to previous MAGICS models.

The MAGICS series has been recognized as the de facto standard tool of mask blank inspection for many years, earning high reputation and confidence among customers around the world. MAGICS models have been widely used for outgoing inspection at mask blank manufacturers and for incoming inspection and process management at mask shops.

EUV mask technology has been making advancements recently, including the introduction of new mask architectures, to enable the further scaling of device geometries. Amid this trend, mask blank inspection also needs to achieve higher performance and better functionality. In order to meet this next-generation need, Lasertec has developed M9750/51, leading-edge inspection systems that provide the high sensitivity required for the defect inspection of advanced EUV mask blanks and substrates².

Drawing on the core technology of MAGICS, M9750/51 have achieved significantly improved sensitivity in the detection of minute defects by introducing newly designed inspection optics and adopting high-speed inspection circuitry from our patterned mask inspection systems. M9750/51 have also introduced a high-precision XY stage for greatly enhanced defect coordinate accuracy to enable defect mitigation during EUV mask manufacturing.

We have already received many inquiries and won multiple orders for M9750/51. Lasertec remains committed to facilitating the quality assurance of next-generation high-end mask blanks, as well as to improving incoming inspection and manufacturing process management at mask shops.

- 1: A "mask blank" is an unpatterned photomask (or mask).
- 2: A "substrate" is a glass baseplate used to make a mask blank.

Features

- Delivering both high-sensitivity inspection of high-quality mask blanks for next-generation semiconductors and high throughput required for incoming and outgoing inspection at production facilities
- New inspection optics and high-speed inspection circuitry adopted from our patterned mask inspection systems, combined with the core technology of MAGICS, the de facto standard tool
- Significantly enhanced sensitivity to defects on substrates or on various layers of leading-edge mask blanks, enabling stringent qualification of blanks
- Highly accurate defect coordinates enabling defect mitigation during EUV mask manufacturing
- M9751 supports line & space monitor pattern inspection, offering an effective tool for various needs of process management at mask shops

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Applications

- Detection of minute defects on EUV mask blanks and substrates
- Instant defect review during inspection, and high-magnification review after inspection
- Sizing of minute defects
- Highly accurate capture of defect coordinates



MAGICS Series M9750/51 Mask Blank Inspection and Review Systems

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